

**NEC**

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*Qualification Test Report on NE292 series*

*Prepared on : February 20, 2001*

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*This report presents the qualification test results on NE292series .  
NE292series are Hetero Junction FET die that utilizes hetero junction between Si-doped AlGaAs and undoped InGaAs to create high mobility electrons .*

#### **1. Test Device**

*NE29283B ( 83B : hermetic seal ceramic package )*

#### **2. Qualification test**

*A series of qualification tests consists of following items :*

- 1) High Temperature DC Bias Test*
- 2) High Temperature Reverse Bias Test*
- 3) High Temperature Storage Test*

*The test conditions are shown in Table 1 . The test parameters and criteria are shown in Table 2 .*

#### **3. Test Results**

##### **1) High Temperature DC Bias Test ( HTPT )**

*No failure has been observed in HTPT until 5000 hours . The test results are shown in Table 3 and the change of all parameters are shown in Figure 1 .*

##### **2) High Temperature Reverse Bias Test ( HTBT )**

*No failure has been observed in HTBT until 5000 hours . The test results are shown in Table 3 and the change of all parameters are shown in Figure 2 .*

##### **3) High Temperature Storage Test ( HT )**

*In order to investigate metallurgical stability such as gate , drain and source electrodes , HT-test were performed at  $T_a=227^{\circ}\text{C}$ ,  $259^{\circ}\text{C}$ ,  $295^{\circ}\text{C}$  and  $337^{\circ}\text{C}$  .  
The test results are shown in Table 4 and the change of all parameters are shown in Figure 3 ~ 6 . The failure mode has been confirmed to be VGF degradation .  
The decrease of VGF is considered to be due to gate schottky degradation caused by some metallurgical reaction between Ti of gate metal (Ti-Al) and AlGaAs in gate recess.  
The Weibull plots and the Arrhenius plots are shown in Figure 7 and 8 respectively .  
They were plotted according to the results under the failure mode of  $\Delta\text{VGF} = -20\%$  .  
The MTTF value at the channel temperature of  $125^{\circ}\text{C}$  was estimated to be  $4.0 \times 10^8$  hours under the failure mode of  $\Delta\text{VGF} = -20\%$  ( activation energy of  $1.86\text{eV}$  ) .*

#### **4. Conclusion**

*From above-mentioned HT-test result , the MTTF value of NE29283B is estimated to be  $4.0 \times 10^8$  hours at the channel temperature of  $125^{\circ}\text{C}$  .*

*Moreover , no failure has been observed in HTPT and HTBT until 5000 hours .*

*Therefore , the NE292series demonstrates high reliability performance for the operating at channel temperature of  $125^{\circ}\text{C}$  and below .*

Table 1. Qualification test item and test condition

Test Item	Test Condition	Quantity	Remarks
High Temperature DC Bias Test	$T_{ch}=175^{\circ}\text{C}$ , $V_{ds}=3\text{V}$ , $I_{ds}=15\text{mA}$ $t=5000\text{hr}$ , up to $F(t)>50\%$	20pcs	No degradation up to 5000hr
High Temperature Reverse Bias Test	$T_a=150^{\circ}\text{C}$ , $V_{gss}=-2.4\text{V}$ $t=5000\text{hr}$ , up to $F(t)>50\%$	20pcs	No degradation up to 5000hr
High Temperature Storage Test	$T_a=227^{\circ}\text{C}$ , $259^{\circ}\text{C}$ , $295^{\circ}\text{C}$ , $337^{\circ}\text{C}$	each 10pcs	No degradation up to 5000hr

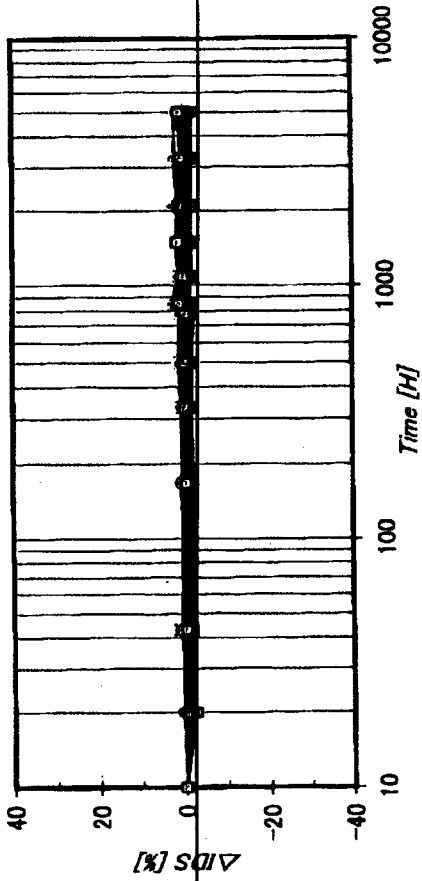
Table 2. Electrical parameter and Criteria

Electrical Parameter	Symbol	Test Condition	Delta Criteria
Gate to Source Forward Voltage	$V_{F(GS)}$	$V_{GS} = 1\mu A$	$\pm 20\%$
Gate to Source Leak Current	$I_{GSO}$	$V_{GS} = -3V$	+300nA or +100% whichever is greater
Drain Current	$I_{DS}$	$V_{DS} = 0.5V, V_{GS} = 0V$	$\pm 20\%$
Saturated Drain Current	$I_{DSS}$	$V_{DS} = 2.0V, V_{GS} = 0V$	$\pm 20\%$
Transconductance	$g_m$	$V_{DS} = 2.0V, I_{DS} = 10mA$	$\pm 20\%$
Gate to Source Cutoff Voltage	$V_p$	$V_{DS} = 2.0V, I_{DS} = 100\mu A$	$\pm 20\%$

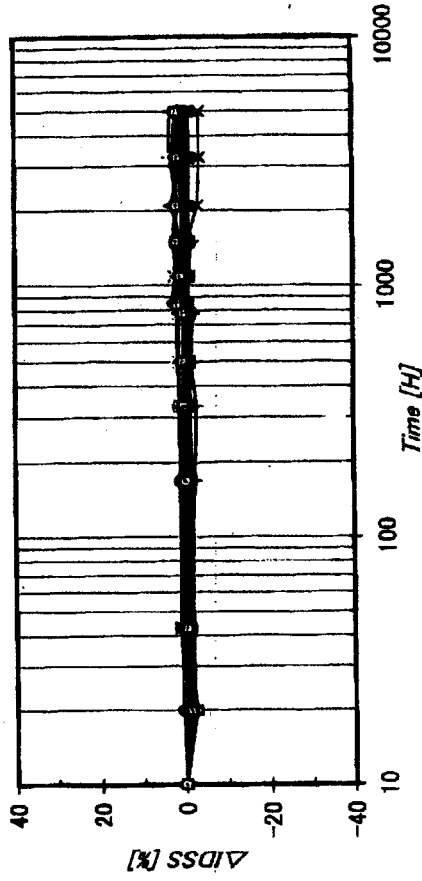




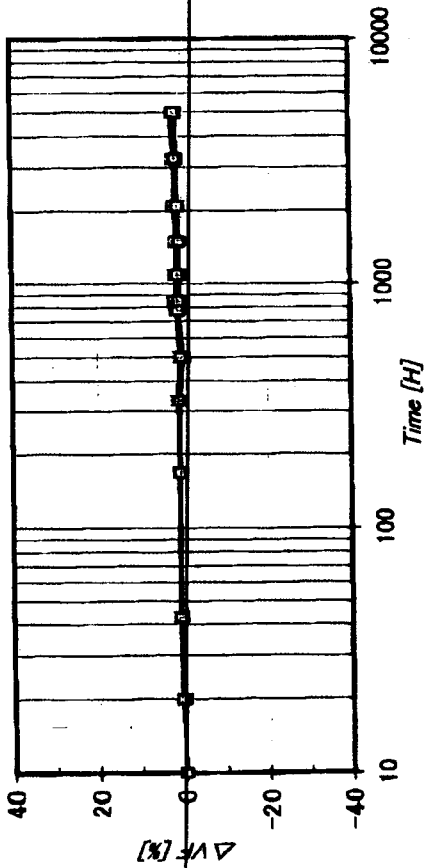
(c)  $ID_{SS}@V_{DS}=0.5V, V_{GS}=0V$



(d)  $ID_{SS}@V_{DS}=2V, V_{GS}=0V$



(a)  $V_F(GS)@I_F=1\mu A$



(b)  $I_{GSO}@V_{GS}=-3V$

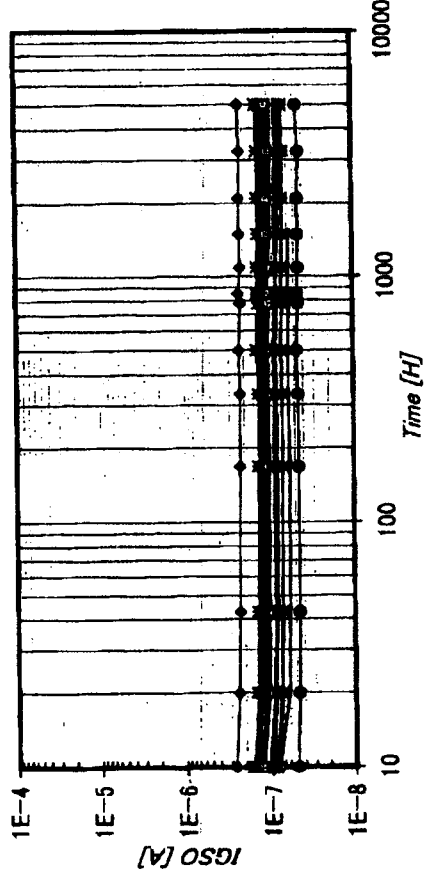


Figure 1-1. High Temperature DC Bias Test Results (  $T_{ch}=175^{\circ}C, V_{ds}=3V, I_{ds}=15mA$  )

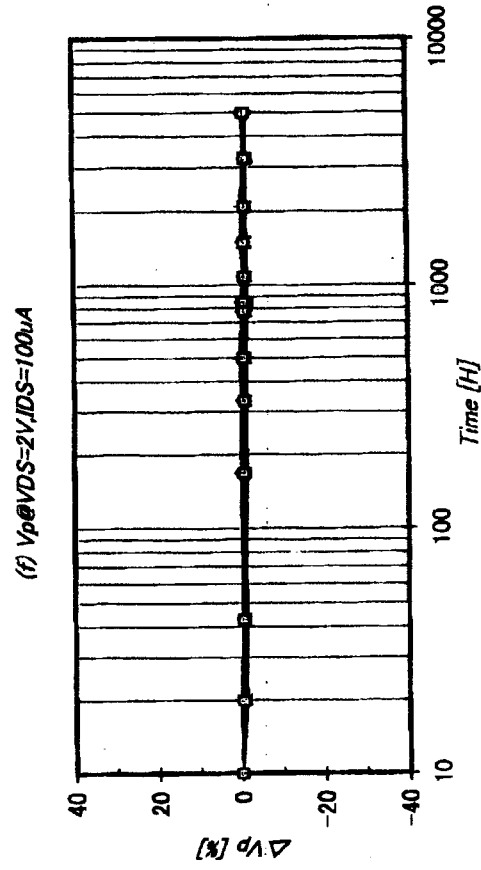
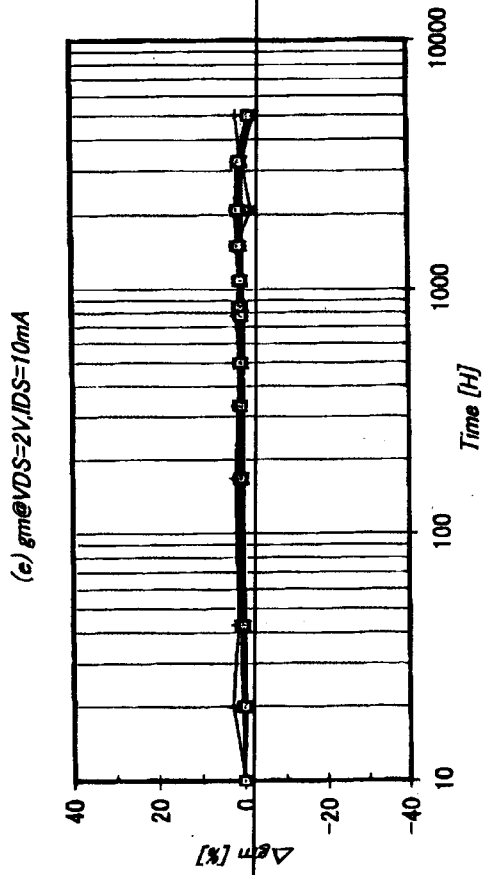


Figure 1-2. High Temperature DC Bias Test Results (  $T_{ch}=175^{\circ}C, V_{ds}=3V, I_{ds}=15mA$  )



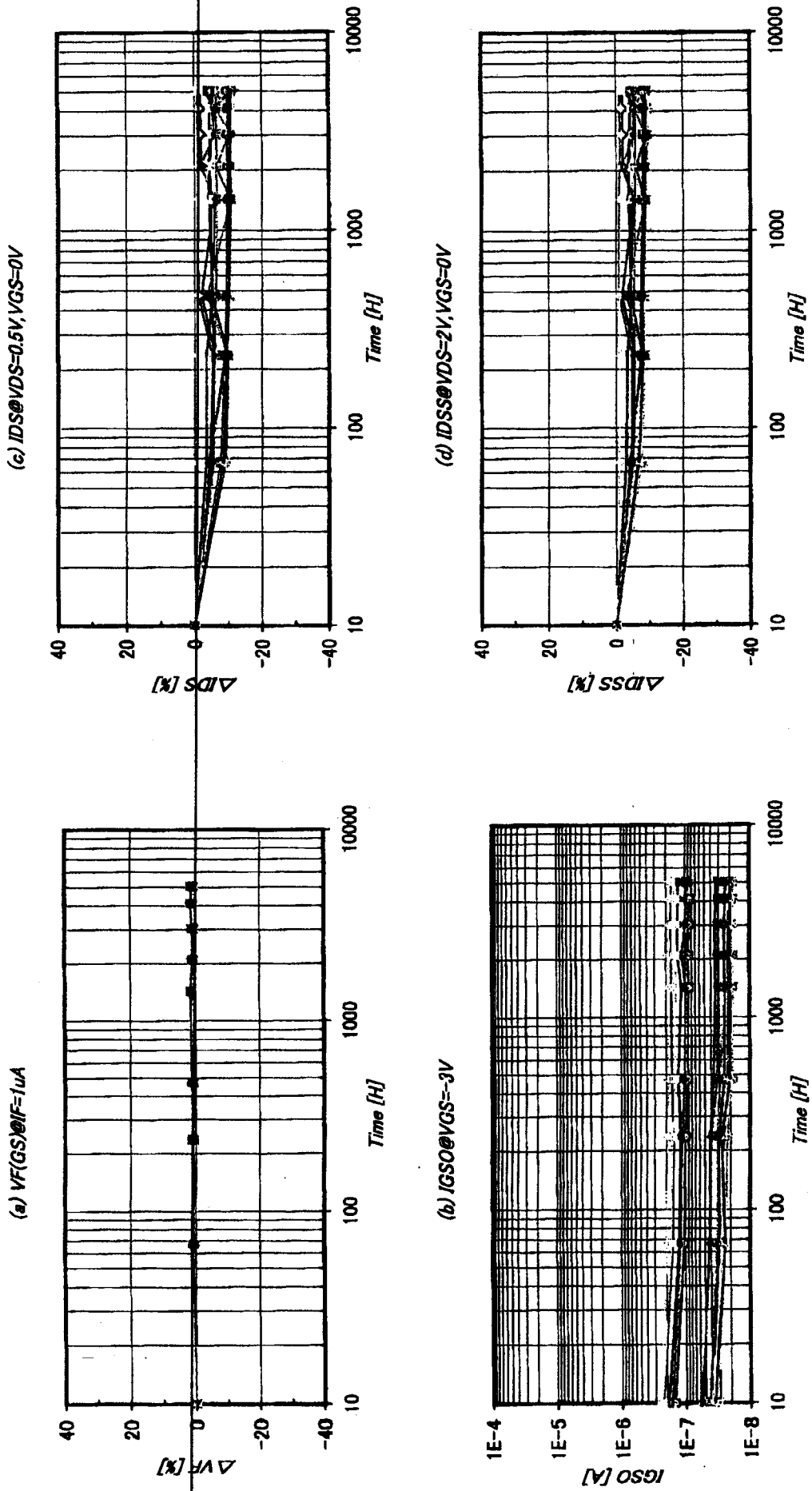


Figure 2-1. High Temperature Reverse Bias Test Results ( $T_a = 150^\circ C, V_{gss} = -2.4V$ )

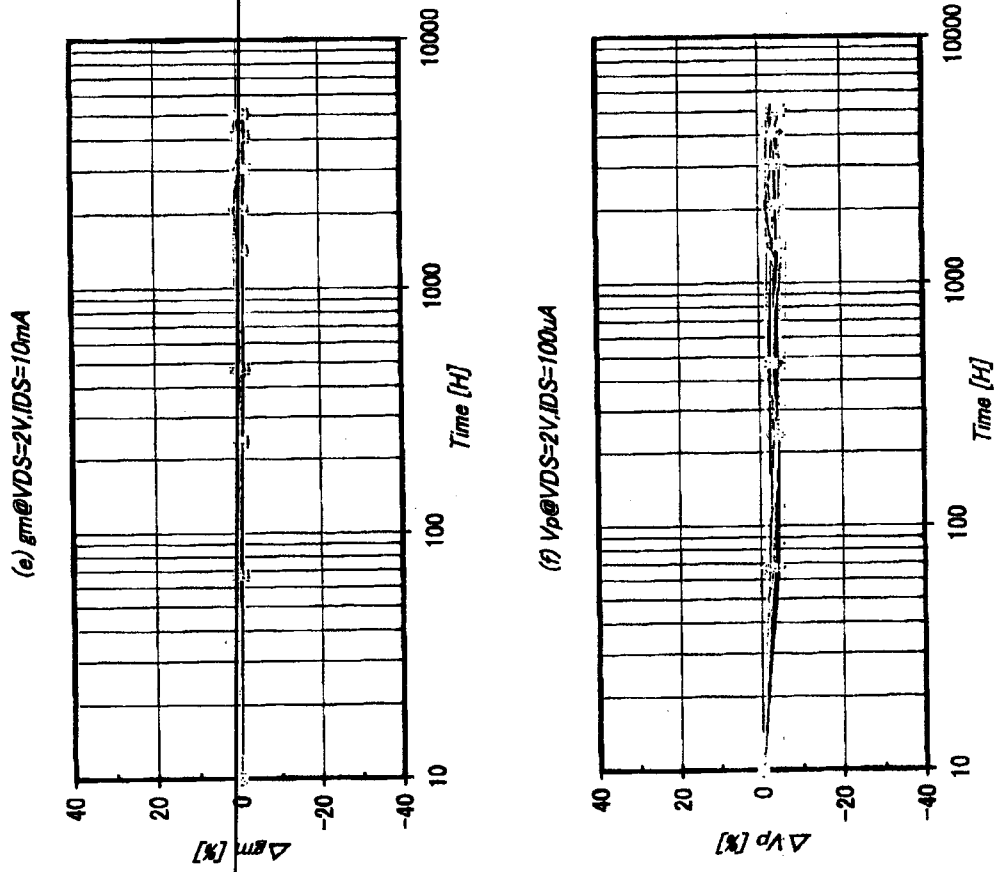


Figure 2-2. High Temperature Reverse Bias Test Results (  $T_a=150^{\circ}C, V_{gss}=-2.4V$  )

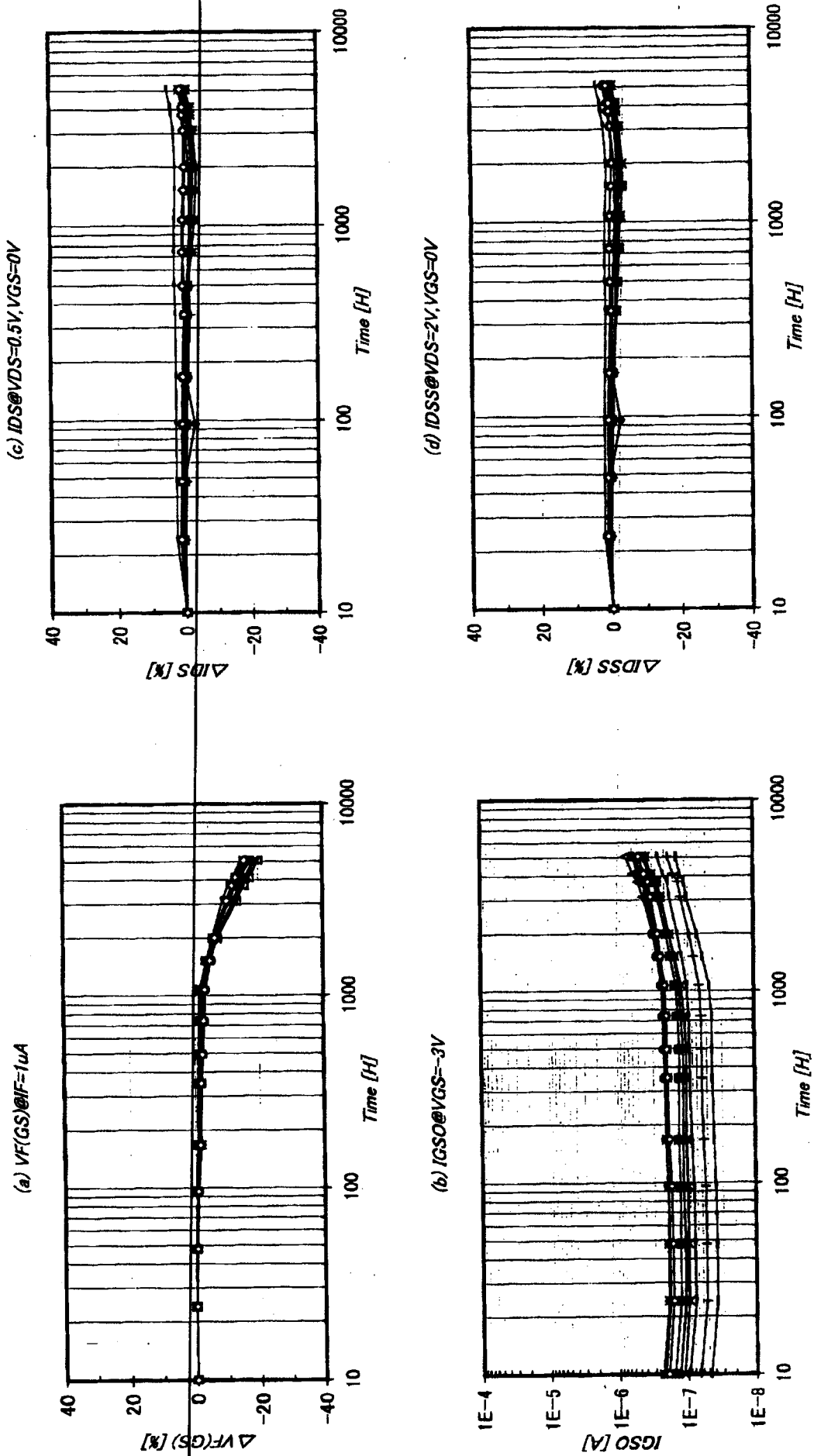


Figure 3-1. High Temperature Storage Test Results (  $T_a = 227^\circ C$  )

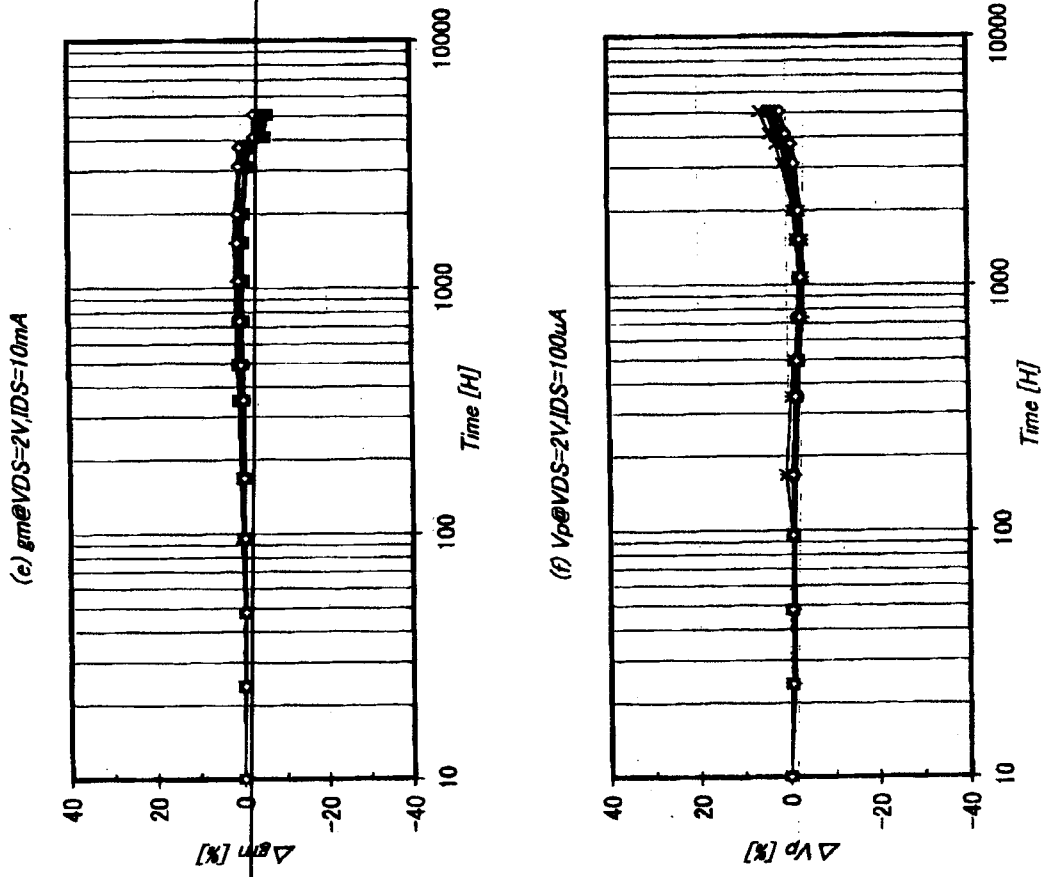


Figure 3-2. High Temperature Storage Test Results (  $T_a=227^{\circ}C$  )

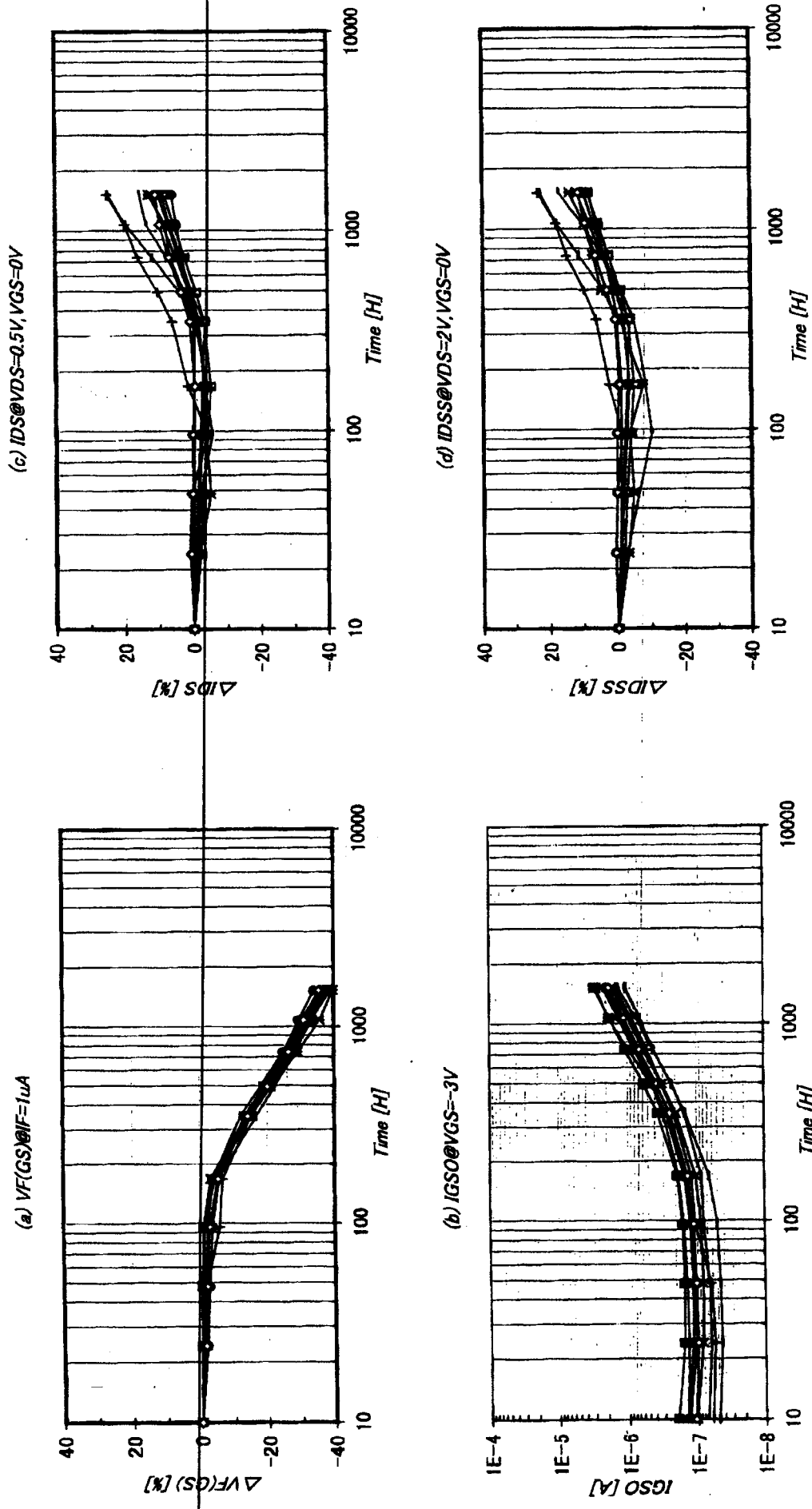


Figure 4-1. High Temperature Storage Test Results (  $T_a=259^\circ C$  )

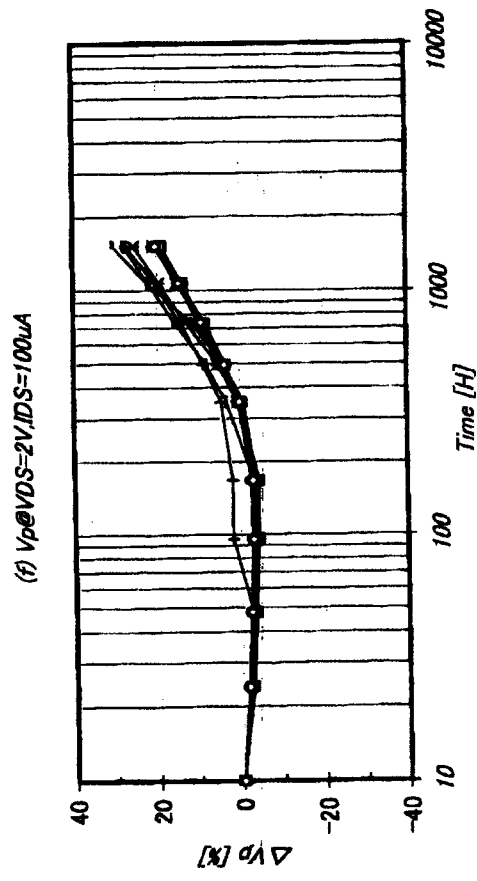
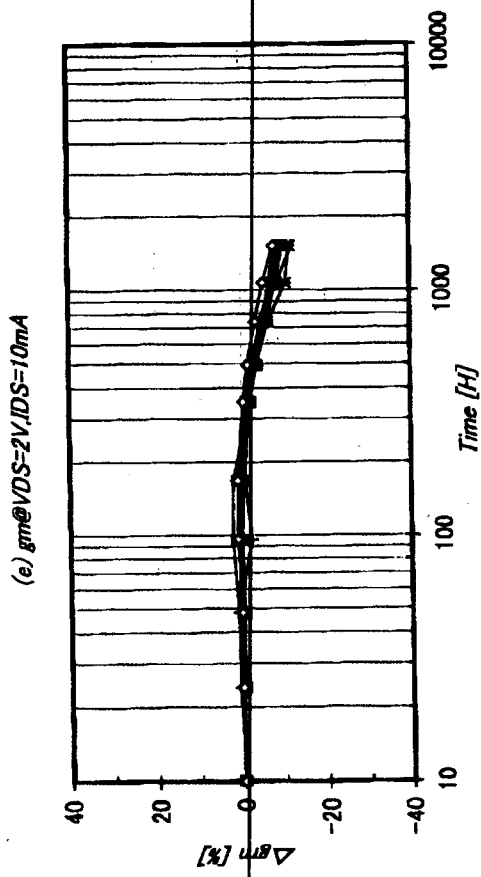


Figure 4-2. High Temperature Storage Test Results (  $T_a=259^{\circ}C$  )

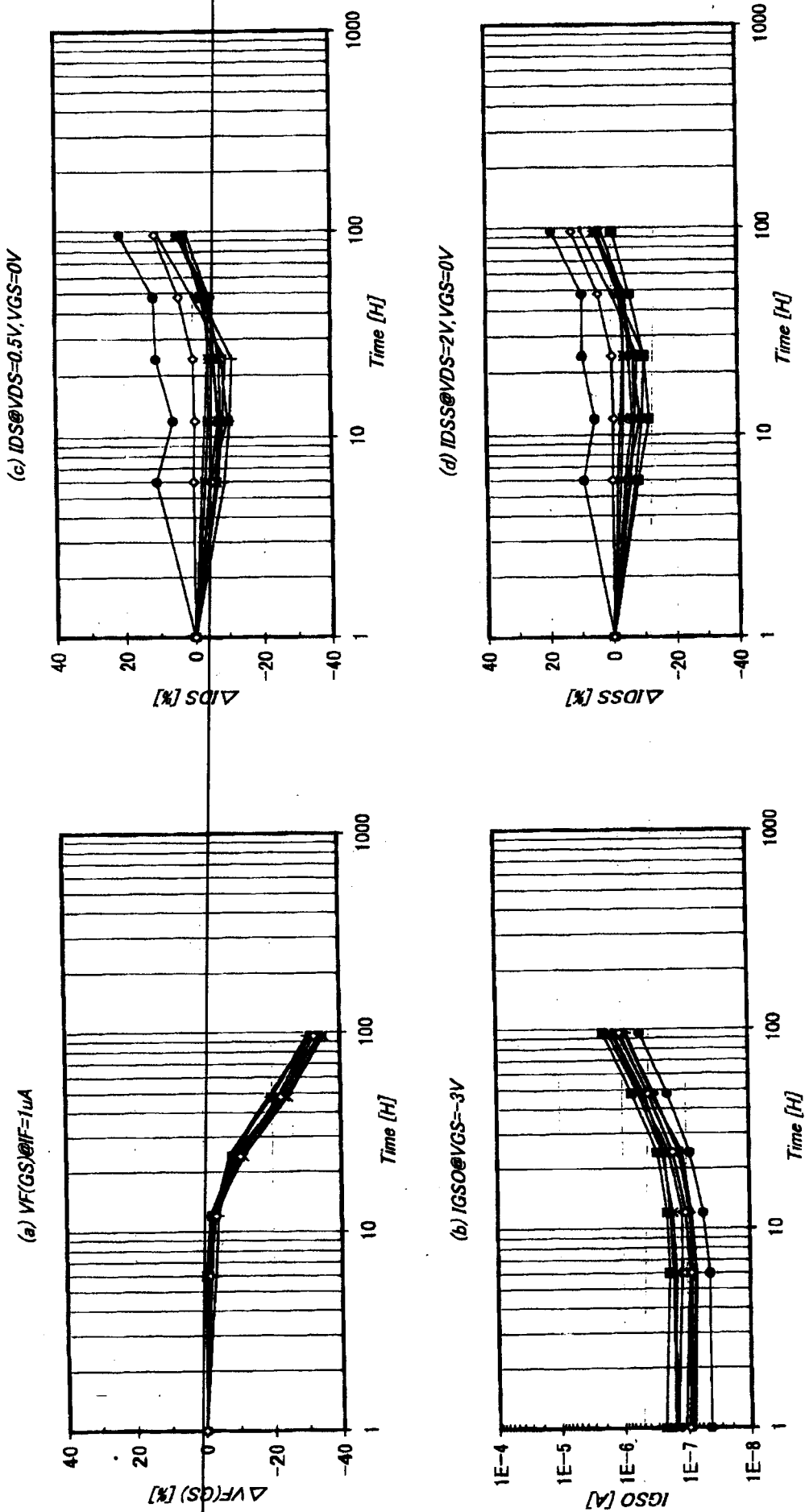


Figure 5-1. High Temperature Storage Test Results (  $T_a=295^{\circ}C$  )

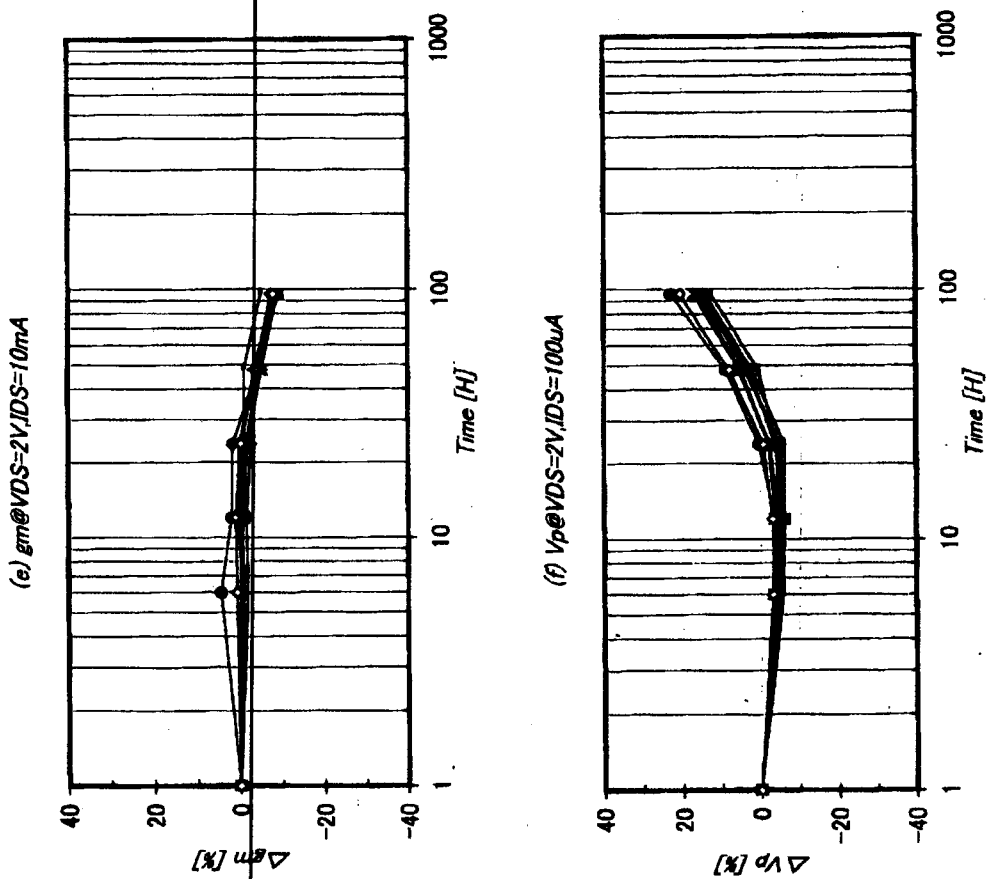


Figure 5-2. High Temperature Storage Test Results (  $T_a=295^\circ C$  )



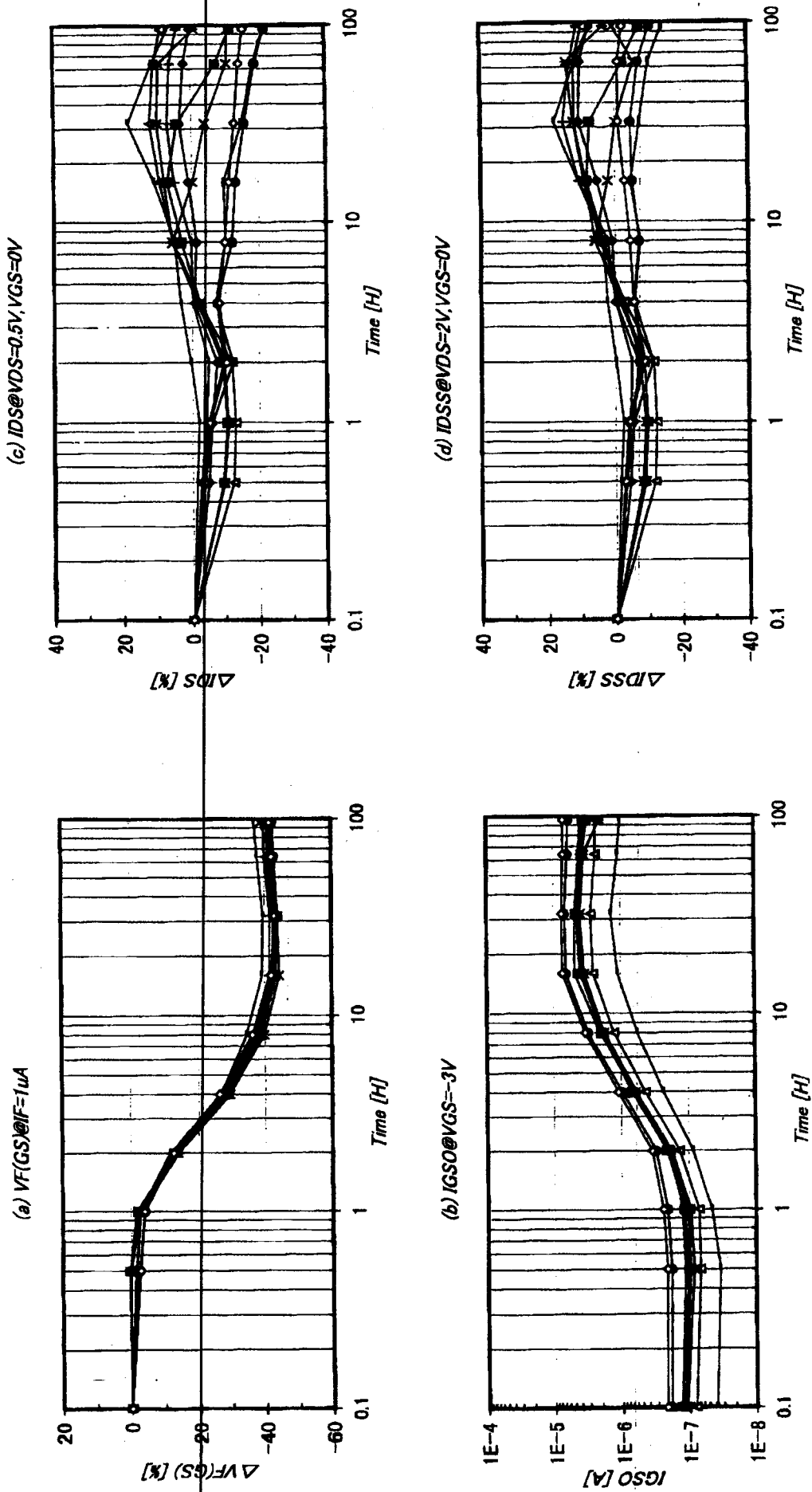


Figure 6-1. High Temperature Storage Test Results (  $T_a=337^\circ C$  )

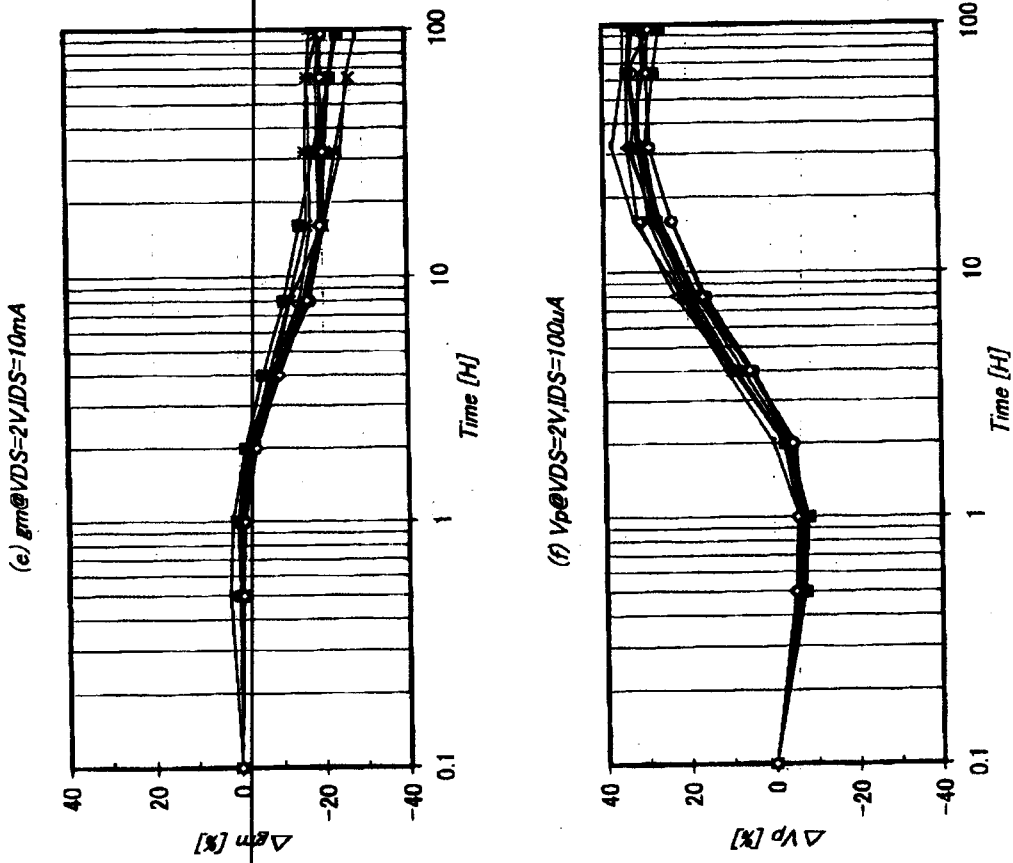


Figure 6-2. High Temperature Storage Test Results (  $T_a=337^{\circ}C$  )

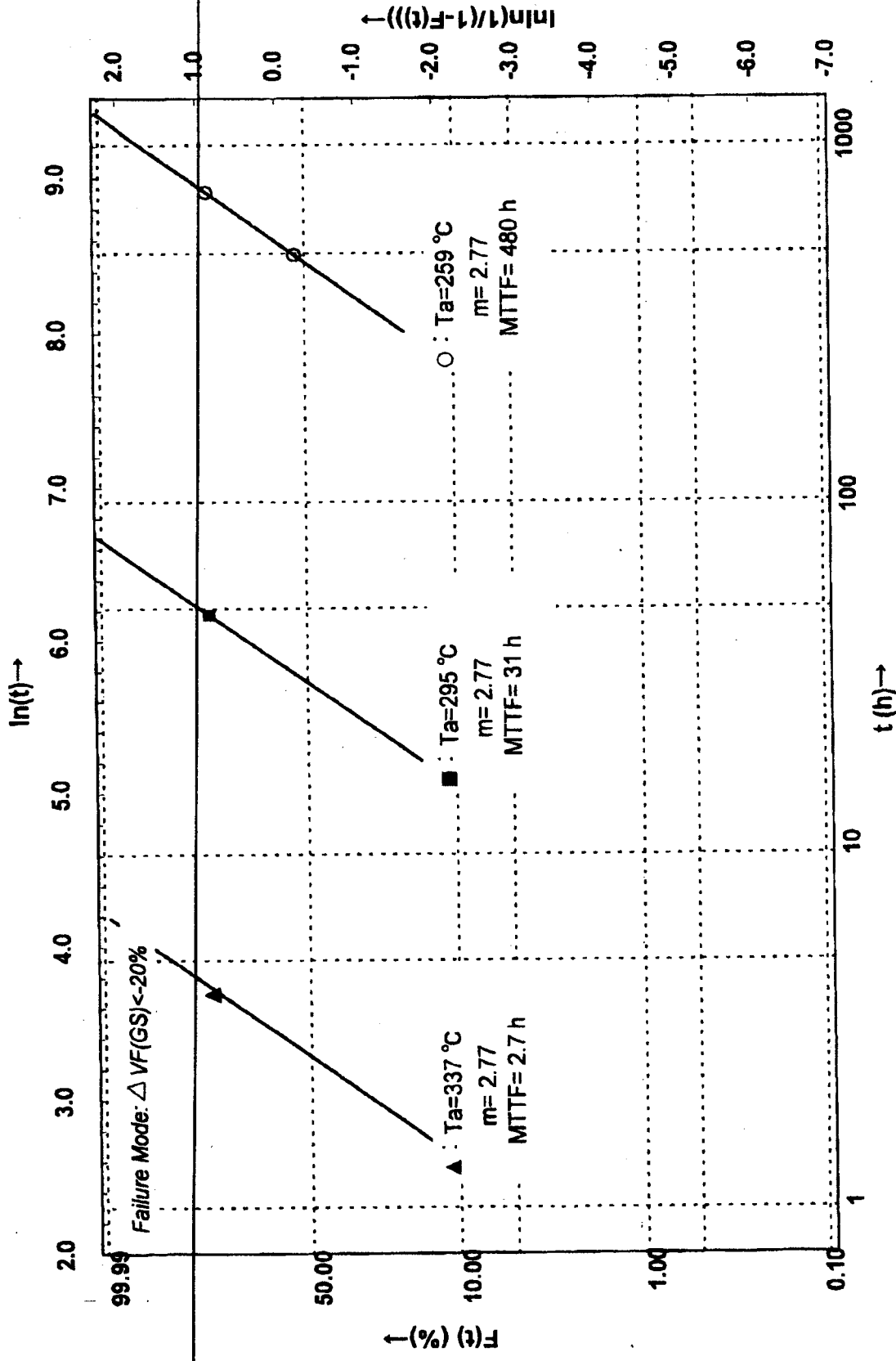


Figure 7 Weibull plots on High Temperature Storage Test Results

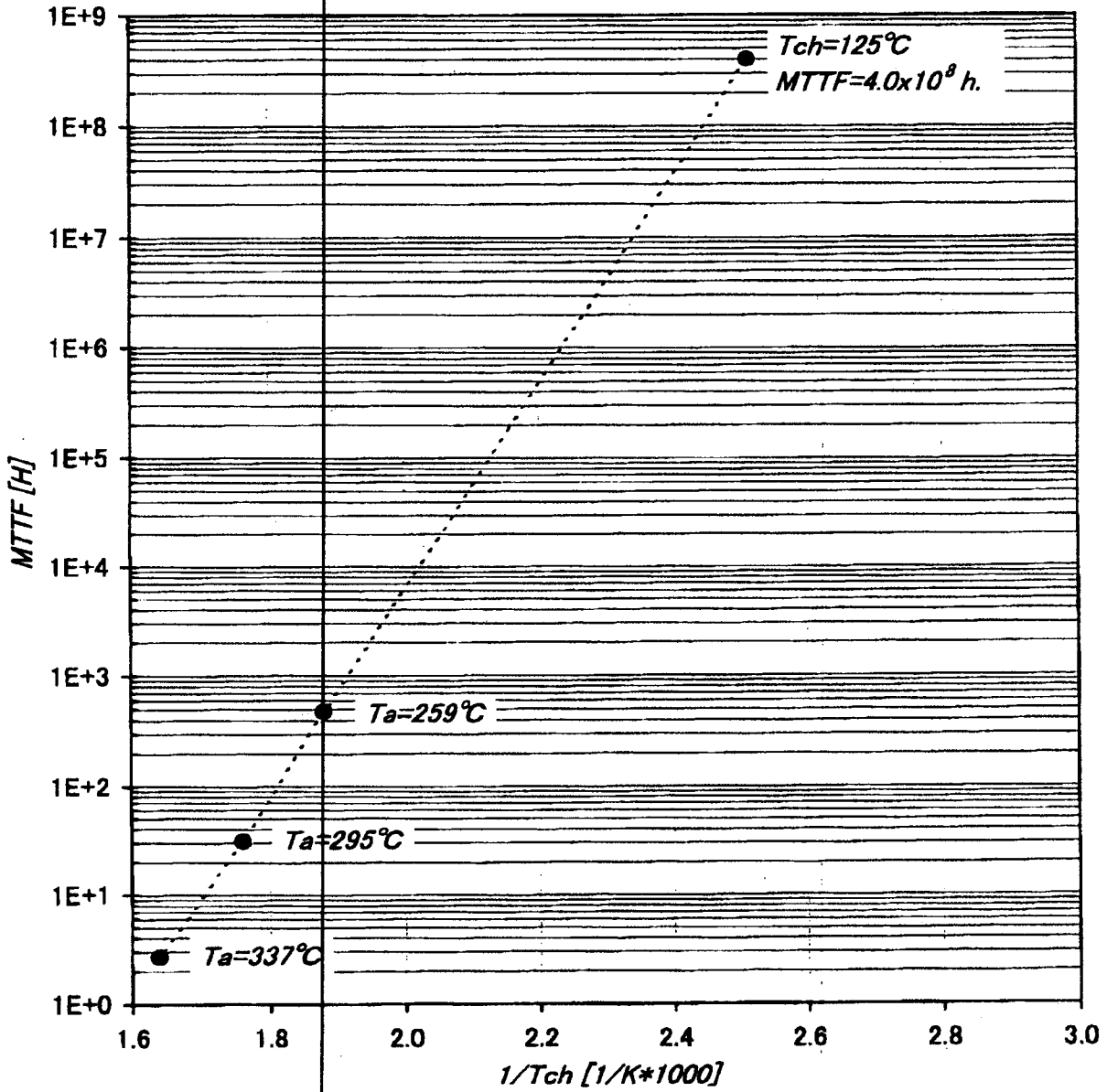


Figure 8. Arrhenius plots on High Temperature Storage Test Results